



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **NIHEI, Mizuhisa, et al.**

Group Art Unit: **2813**

Serial No.: **10/796,146**

Examiner: **PHAM, Thanhha S.**

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For. **SEMICONDUCTOR DEVICE AND MANUFACTURING METHOD THEREOF**

INFORMATION DISCLOSURE STATEMENT AND
STATEMENT PURSUANT TO 37 CFR 1.97(c)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

March 5, 2008

Sir:

The attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached Form PTO-1449. One copy of each of these documents, except U.S. Patent references, is attached.

This Information Disclosure Statement is being submitted after issuance of a first official action on the merits and expiration of the three month period following the filing date or the entry in the national stage for the above-captioned application, but prior to issuance of either a final official action, a Notice of Allowance, or an action that otherwise closes prosecution in the application.

The undersigned hereby certifies

XX that each item of information contained in this statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.